AMENDMENTS TO THE CLAIMS:

Please cancel Claims 3, 7, and 18 without prejudice to or disclaimer of the subject matter recited therein.

Please amend Claims 1, 2, 4 through 6, 10, 11, 14, 15, 17, 19, and 20 as follows:

1. (Currently Amended) A structure comprising a first area including a plurality of pores ~~which have a first period~~ arranged in a lattice structure that is one of (a) a hexagonal lattice, (b) a rectangular lattice, and (c) a graphite-shaped lattice, and a second area including a plurality of pores ~~which have a second period, characterized in that~~ arranged in a lattice structure that is a different one of (a), (b), and (c),

wherein the first area and the second area share a plurality of pores at a boundary of the lattice structure of the first area and the lattice structure of the second area, and

wherein the first area's pore interval is the same as the second area's pore interval.

2. (Currently Amended) A structure comprising periodic array structures of pores formed in an anodized oxide film, wherein a plurality of types of periodic array structures are arranged adjacent to one another including (i) a first structure that is one of (a) a hexagonal lattice, (b) a rectangular lattice, and (c) a graphite-shaped lattice, and (ii) a second structure that is a different one of (a), (b), and (c),

wherein the first structure and the second structure have pores in common on a boundary therebetween, and

wherein in an area occupied by the first structure and in an area occupied by the second structure, the pore interval is the same.

3. (Cancelled)

4. (Currently Amended) The structure according to claim 2, wherein ~~a plurality of types of the periodic array structures~~ the first structure and the second structure have at least one pore in addition to the pores in ~~the shared region~~ common.

5. (Currently Amended) The structure according to claim 2, wherein ~~a plurality of types of the periodic array structures~~ the first structure and the second structure each have equal distances between first proximate pores or have the distance between first proximate pores on one side equal to the distance between second proximate pores on the other side or have equal distances between second proximate pores.

6. (Currently Amended) The structure according to claim 5, wherein the distance between the most proximate pores of ~~a plurality of types of the periodic array structures is 0.75B to 1.5B where B is a numerical value [nm] included within the range between a maximum value and a minimum value of the distance between the most proximate pores of the above described plurality of types of periodic array structures~~ each of the first structure and the second structure is 150 nm to 300 nm.

7. (Cancelled)

8. (Original) The structure according to claim 2, wherein said anodized oxide film is comprised of aluminum as a principal component.

9. (Original) The structure according to claim 2, wherein at least one of said pores includes a filler.

10. (Currently Amended) The structure according to claim 9, wherein said filler is (a) a dielectric having a dielectric constant different from that of said anodized oxide film, (b) a semiconductor, (c) a magnetic material, or (d) a light-emitting material.

11. (Currently Amended) An optical device wherein said pores of the structure according to claim 2 are filled with a dielectric having a dielectric constant different from that of said anodized oxide film.

12. (Original) A light-emitting device wherein said pores of the structure according to claim 2 are filled with a light-emitting material.

13. (Original) A magnetic device wherein said pores of the structure according to claim 2 are filled with a magnetic material.

14. (Currently Amended) A magnetic recording medium comprising:

a data area where pores filled with ~~said~~ magnetic material to record information; and

a servo area where track positions are detected,

~~wherein the structure made up of simple periodic arrays of said pores differs between said data area and said servo area~~ wherein said data area comprises pores arranged in a structure that is one of (a) a hexagonal lattice, (b) a rectangular lattice, and (c) a graphite-shaped lattice,

wherein said servo area comprises pores arranged in a structure that is a different one of (a), (b), and (c),

wherein said data area's structure and said servo area's structure have pores in common at a boundary therebetween, and

wherein said data area's pore interval is the same as said servo area's pore interval.

15. (Currently Amended) The magnetic recording medium according to claim 14, wherein at least one pore in said servo area is shifted by half a period with respect to ~~the~~ a period of pores perpendicular to the track direction in the data area.

16. (Original) The magnetic recording medium according to claim 14, wherein said servo area is constructed of at least two types of periodic array structures.

17. (Currently Amended) A method of manufacturing a structure in which a plurality of pore periodic array structures formed in an anodized oxide film having

different periods are arranged adjacent to one another, said method comprising:

(1) a step of forming pore starting points made up of a plurality of types of periodic arrays on the surface of a substrate comprised of aluminum as a principal component; and

(2) a step of anodizing said ~~substrate~~ substrate's pore starting points simultaneously at the same anodization voltage,

wherein the plurality of pore periodic array structures comprise (i) a first structure that is one of (a) a hexagonal lattice, (b) a rectangular lattice, and (c) a graphite-shaped lattice, and (ii) a second structure that is a different one of (a), (b), and (c),

wherein the first structure and the second structure have pores in common on a boundary therebetween, and

wherein in an area occupied by the first structure and in an area occupied by the second structure, the pore interval is the same.

18. (Cancelled)

19. (Currently Amended) The method of manufacturing a structure according to claim 17, wherein ~~said plurality of periodic array structures~~ the first structure and the second structure ~~having different periods~~ have at least one pore in addition to the pores in ~~said shared region~~ common.

20. (Currently Amended) The method of manufacturing a structure according to claim 17, wherein a voltage applied during anodization of the structure of said plurality of

periodic arrays is A volts, and ~~[V] (B [nm] = A [V]/2.5 [V/nm], where [[B]] nanometers is~~

wherein the following condition is satisfied:

B = A/(2.5 volts/nanometer)

where B is ~~a numerical value included~~ within the range between a maximum value and a minimum value of the distance between the most proximate pores included in said plurality of ~~types of~~ pore periodic array ~~structures)~~ structures.